

6,153,504 Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. M122-2497	SERIAL NO. 10/776,553
LIST OF REFERENCES CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Weimin Li et al.	
		FILING DATE February 10, 2004	GROUP 2811

U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
P	AA	6,153,504	11-2000	Shields et al.			
O	AB	4,971,655	11-1990	Stefano et al.			
	AC						
	AD						
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	AG						
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	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
B	AM	08-045926A	02-1996	Japan (abstract)				
C	AN	10-163083	06-1998	Japan			x	
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
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	AS		
	AT		

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Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. M122-2497	Priority SERIAL NO. 10/776,553
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Weimin Li et al.	
		Priority FILING DATE August 17, 2000	GROUP Unknown

U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
G	AA	4,474,975	10/84	Clemons et al.			
0	AB	5,962,581	10/99	Hayase et al.			
	AC	5,677,015	10/97	Hasegawa			
	AD	5,783,493	07/98	Yeh et al.			
	AE	5,807,660	09/98	Lin et al.			
	AF	4,833,096	05/89	Huang et al.			
	AG	5,405,489	04/95	Kim et al.			
	AH	5,470,772	11/95	Woo			
	AI	5,652,187	07/97	Kim et al.			
	AJ	5,656,337	08/97	Park et al.			
	AK	4,805,683	2/89	Magdo et al.			
	AL	5,874,367	2/99	Dobson			
	AM	5,858,880	1/99	Dobson et al.			

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AN	0-942330	9/99	EPO				
0	AO	9-50993	02/97	Japan				X
	AP	0-234172	09/94	Japan				X
0	AQ	593,727	10/47	GB				


OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
0	AR	withheld Weidman, R. et al., "Matrix Reactions of Methylsilanes and Oxygen Atoms", The Journal of Physical Chemistry, Vol. 92, No. 3, 1998, pp. 594-602.
0	AS	Weidman, T. et al., "New Photodefinable Glass Etch Masks for Entirely Dry Photolithography: Plasma Deposited Organosilicon Hydride Polymers", Appl. Phys. Lett., Vol. 62, No. 4, Jan. 25, 1993, pp. 372-374.
0	AT	Weidman, T. et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon Dioxide Precursor", J. Photopolym. Sci. Technol., Vol. 8, No. 4, 1995, pp. 679-686.

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. 09/644,826		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.		Priority FILING DATE August 17, 2000		
						GROUP Unknown		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
Q	AA	5,219,613	6/93	Fabry et al.	/	/		
	AB	5,270,267	12/93	Ouellet	/	/		
	AC	5,541,445	7/96	Quellet	/	/		
	AD	6,022,404	02/00	Ettlinger et al.	/	/		
	AE	5,709,741	01/98	Akamatsu et al.	/	/		
	AF	4,648,904	03/87	DePasquale et al.	/	/		
	AG	4,158,717	06/79	Nelson	/	/		
	AH	5,667,015	09/97	Harestad et al.	/	/		
	AI	5,661,093	8/97	Ravi et al.	/	/		
	AJ	5,536,857	7/96	Narula et al.	/	/		
	AK	4,695,859	9/87	Guha et al.	/	/		
	AL	5,061,509	10/91	Naito et al.	/	/		
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
Q	AM	5-263255	10/93	Japan	/	/	Yes	No
	AN	0-464515 A3	01/92	EPO	/	/		X
Q	AO	0-771886 A1	05/97	EPO	/	/		
	AP	63-157443	06/88	JP	/	/	X	
	AQ	0-471185 A3	02/92	EPO	/	/		
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
Q	AR	Joubert, O. et al., "Application of Plasma Polymerized Methylsilane in an All Dry Resist Process for 193 and 248nm Lithography".						
		Microelectronic Engineering 30 (1996), pp. 275-278.						
Q	AS	Joshi, A. et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV						
		Photolithography", SPIE Vol. 1925 (1993), pp. 709-720.						
Q	AT	Matsura, M. et al., "A Highly Reliable Self-Planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects. IEEE						
		IEDM Tech. Dig., 1997, pp. 785-788.						
EXAMINER e				DATE CONSIDERED 11/5/05				

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. 097841,826		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			Priority FILING DATE August 17, 2000	
								GROUP Unknown	
U.S. PATENT DOCUMENTS									
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
G	AA	4,600,671	7/86	Saitoh et al.					
	AB	5,753,320	5/98	Mikoshiba et al.					
	AC	5,356,515	10/94	Tahara et al.					
	AD	5,731,242	3/98	Parat et al.					
	AE	6,054,379	4/00	Yau et al.					
	AF	5,948,482	9/99	Brinker et al.					
	AG	5,800,877	9/98	Maeda et al.					
	AH	5,260,600	11/93	Harada					
	AI	4,992,306	2/91	Hochberg et al.					
	AJ	4,702,936	10/87	Maeda et al.					
	AK	4,863,755	9/89	Hess et al.					
	AL	5,234,869	8/93	Mikata et al.					
FOREIGN PATENT DOCUMENTS									
		Document Number	Date	Country	Class	Subclass	Translation		
							Yes	No	
	AM	0 388007 A25	03/94	EPO					
		9-065851	02/97	JP					
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)									
O	AN	Horic, O. et al., "Kinetics and Mechanism of the Reactions of O(³ P) with SiH ₄ , CH ₃ SiH ₃ , (CH ₃) ₂ SiH ₂ , and (CH ₃) ₃ SiH", J. Phys. Chem. 1991, Vol. 95, pp. 4393-4400.							
Q	AO	McClatchie, S. et al., "Low Dielectric Constant Flowfill" Technology for IMD Applications", Proceed. of 3d Internat. Dielectrics for ULSI Multilevel Interconnection Conf, Santa Clara, CA, Feb. 1997, pp. 34-40.							
	AP	Beekman, K. et al. "Sub-Micron Gap Fill and In-Situ Planarisation Using Flowfill" Technology", ULSI Conf, Portland, OR, Oct. 1995, pp. 1-7.							
	AQ	Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-2.							
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. 097041,020	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
G	AA	5,302,366	4/94	Schuette et al.				
	AB	5,591,494	1/97	Sato et al.				
	AC	5,968,611	10/99	Kaloyeros et al.				
	AD	6,159,871	12/00	Loboda et al.				
	AE	5,461,003	10/95	Havemann et al.				
	AF	6,124,641	9/00	Matsuura				
	AG	5,554,567	9/96	Wang				
	AH	6,028,015	2/00	Wang et al.				
	AI	5,744,399	4/98	Rostoker				
	AJ	5,883,014	3/99	Chen				
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AK	0-728496-A2	03/96	EPO				
	AL	06-067019A	03/94	JP (abstract)				
	AM	H72845-A3	01-2002	EPO				
	AN	08-213386A	08-1996	Japan				
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
G	AO	IBM Technical Disclosure Bulletin, "Low-Temperature Deposition of SiO ₂ , Si ₃ N ₄ , or SiO ₂ -Si ₃ N ₄ ", Vol. 28, Iss. 9, p. 4170 (Feb. 1986).						
	AP	IBMT: Rulla, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 312-313.						
Q	AO	ABSTRACT: Loboda, M. et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes".						
		Electrochemical Society Meeting Abstract No. 358, 191 st Meeting, Montreal, Quebec, Vol. MA 97-1, 1997, page 454.						
Q	AR	Laxman, R. et al., "Synthesizing Low-K CVD Materials for Fab Use", Semiconductor Internatl., Nov. 2000, pp. 95-102 (printed from						
		www.semiconductor-intl.com).						
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L					4/15/05			
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2497		Priority SERIAL NO. 02/641826	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000			GROUP Unknown
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,017,779	1/00	Miyasaka				
	AB	6,156,674	12/00	Li et al.				
	AC	6,140,151	10/00	Akram				
	AD	5,314,724	5/94	Tsukune et al.				
	AE	5,376,591	12/94	Maeda et al.				
	AF	5,817,549	10/98	Yamazaki et al.				
	AG	6,072,227	6/00	Yau et al.				
	AH	6,001,741	12/99	Alers				
	AI	5,786,039	7/98	Brouquet				
	AJ	6,235,568 B1	5/01	Murthy et al.				
	AK	6,187,694 B1	2/01	Cheng et al.				
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	200068261A	03-2000	Japan				
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM		Anonymous, "New Gas Helps Make Faster ICs", Machine Design, Vol. 71, Iss. 21, Nov. 4, 1999, p. 118.					
	AN		Grant 1, "Hatch's Chemical Dictionary", McGraw-Hill, Inc. 1969, Fourth Edition, page 27.					
	AO		Wolf, S. et al. , "Silicon Processing for the VLSI Era", Vol. 1, pp. 437-441.					
	AP		McKenzie, D.R. et al., "New Technology for PACVD", Surface and Coatings Technology, Vol. 62, pp. 326-333 (1996).					
	AO		Shibata, N., "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Jap. Jour. of App. Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.					
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Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. M122-2497	Priority SERIAL NO. 09644-026
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Weimin Li et al.	
		Priority FILING DATE August 17, 2000	GROUP Unknown

U.S. PATENT DOCUMENTS							
*Examiner Initial	Class	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
G	AA	5,750,442	5/98	Juengling			
	AB	6,114,255	9/00	Juengling			
	AC	6,238,976 B1	5/01	Noble et al.			
	AD	6,008,121	12/99	Yang et al.			
	AE	5,140,390	8/92	Li et al.			
	AF	5,286,661	2/94	de Fresart et al.			
	AG	6,184,151 B1	2/01	Adair et al.			
	AH	6,225,217 B1	5/01	Usami et al.			
	AI	6,004,850	12/99	Lucas et al.			
	AJ	6,140,677	10/00	Gardner et al.			
	AK	6,133,096	10/00	Su et al.			
	AL	6,136,636	10/00	Wu			

FOREIGN PATENT DOCUMENTS							
Class	Subclass	Document Number	Date	Country	Class	Subclass	Translation
							Yes No
		AM 868887A	09-1999	TW			

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
AN		Bencher, C. et al., "Dielectric Antireflective Coatings for DUV Lithography" Solid State Technology (March 1997), pp. 109-114.
AO		Dammel, R. B., et al., "Dependence of Optical Constants of AZ™ BARL™ Bottom Coating on Back Conditions, SPIE Vol. 3049 (1997), pp. 963-973.
AP		TEXT: Heavens, O.S., "Optical Properties of Thin Solid Films", pp. 48-49.
AQ		TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10.

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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclasses	Filing Date If Appropriate	
↕	AA	5,933,721	8/99	Hause et al.	_____	_____		
	AB	5,981,368	11/99	Gardner et al.	_____	_____		
	AC	6,159,804	12/00	Gardner et al.	_____	_____		
	AD	6,130,168	10/00	Chu et al.	_____	_____		
	AE	6,235,591 B1	5/01	Balasubramanian et al.	_____	_____		
	AF	6,198,144 B1	3/01	Pan et al.	_____	_____		
	AG	5,801,399	9/98	Hattori et al.	_____	_____		
	AH	5,994,730	11/99	Shrivastava et al.	_____	_____		
	AI	6,040,619	3/00	Wang et al.	_____	_____		
	AJ	6,060,765	5/00	Maeda	_____	_____		
	AK	6,060,766	5/00	Mehta et al.	_____	_____		
	AL	6,451,504	09/02	Rolfson et al.	_____	_____		
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM	429473A	04-2001	TW	_____	_____		
	AN	429844A	02-2001	TW	_____	_____		
	AO	8046186	02-1996	Japan	_____	_____	X	
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AP	Wolf et al., "Silicon Processing for the VLSI Era - Vol. 1 - Process Technology," Prologue, page xxiii (2 pages total).						
	AQ	Wolf, "Silicon Processing for the VLSI Era, Vol. 2: Process Integration," © 1990, pp. 189-190.						
	AR							
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U.S. PATENT DOCUMENTS								
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a	AA	6,133,613	10/00	Yao et al.				
	AB	6,087,267	07/00	Dockrey et al.				
	AC	5,543,654	08/96	Dennen				
	AD	5,656,330	08/97	Niiyama et al.				
	AE	5,872,035	02/99	Kim et al.				
	AF	4,444,617	04/84	Whitcomb				
	AG	6,071,799	06/00	Park et al.				
	AH	5,691,212	11/97	Tsai et al.				
	AI	6,187,657 B1	02/01	Xiang et al.				
	AJ	5,792,689	08/98	Yang et al.				
	AK	6,281,100 B1	08/01	Yin et al.				
	AL	6,323,101 B1	11/01	Li et al.				
	AM	5,413,963	05-1995	Yen et al.				
	AN	6,143,670	11-2000	Cheng et al.				
	AO	6,403,464	06-2002	Chang				
	AP	4,940,509	07-1990	Tso et al.				
AQ	5,429,987	04-1995	Allen					
FOREIGN PATENT DOCUMENTS								
	Class	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
a		AR 8046188	02-1996	Japan				
a		AS 7201716	08-1995	Japan			X	
a		AT 6232113	08-1994	Japan				
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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U.S. PATENT DOCUMENTS							
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d	AA	4,954,867	09/90	Hosaka			
	AB	5,441,797	08/95	Hogan et al.			
	AC	5,472,827	12/95	Ogawa et al.			
	AD	5,674,356	10/97	Nagayama			
	AE	5,710,067	01/98	Foote et al.			
	AF	5,741,721	04/98	Stevens			
	AG	5,759,755	06/98	Park et al.			
	AH	5,838,052	11/98	McTeer			
	AI	5,472,829	12/95	Ogawa			
	AJ	5,591,566	01/97	Ogawa			
	AK	4,910,160	03-1990	Jennings et al.			
	AL	6,200,835 B1	03-2001	Manning			
	AM	5,244,537	09-1993	Ohnstein			
	AN	6,204,168 B1	03-2001	Naik et al.			
	AO	4,562,091	12-1985	Sachdev et al.			
	AP	4,764,247	08-1988	Leveriza et al.			
AQ	5,986,318	11-1999	Kim et al.				
AR	6,087,064	07-2000	Lin et al.				
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
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U.S. PATENT DOCUMENTS								
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A	AA	5,677,111	10/97	Ogawa				
	AB	5,670,297	09/97	Ogawa et al.				
	AC	5,698,352	12/97	Ogawa et al.				
	AD	5,831,321	11/98	Nagayama				
	AE	5,034,348	07/91	Hartswick et al.				
	AF	5,340,621	8/23/94	Matsumoto et al.				
	AG	5,600,165	2/4/97	Tsukamoto et al.				
	AH	6,008,124	12/99	Sekiguchi et al.				
	AI	5,968,324	10/99	Cheung et al.				
	AJ	5,872,385	02/99	Taft et al.				
	AK	5,883,011	04/99	Lin et al.				
	AL	5,960,289	09/99	Tsui et al.				
	AM	4,755,478	07-1988	Abernathy et al.				
	AN	4,870,470	09-1989	Bass et al.				
	AO	5,312,768	05-1994	Gonzalez				
	AP	5,439,838	08-1995	Yang				
	AQ	6,001,747	12-1999	Annappagada				
AR	6,518,122	02-2003	Chan et al.					
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. 09641870	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			Priority FILING DATE August 17, 2000
							GROUP Unknown	
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*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate		
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FOREIGN PATENT DOCUMENTS								
Document Number	Date	Country	Class	Subclass	Translation			
					Yes		No	
AS								
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
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*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
9	AA	09/234,233	Li et al.					
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	AL							
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AM							
	AN							
	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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